

Title (en)  
UV-RESISTANT ELECTRODE ASSEMBLY

Title (de)  
UV-BESTÄNDIGE ELEKTRODENANORDNUNG

Title (fr)  
ENSEMBLE ÉLECTRODE RÉSISTANT AUX UV

Publication  
**EP 3340253 A1 20180627 (EN)**

Application  
**EP 16206478 A 20161222**

Priority  
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Abstract (en)  
The present invention is therefore to an electrode assembly comprising at least a substrate, a conductive layer formed on the substrate; said conductive layer comprising at least a metal nanowires, and an overcoat layer formed on the conductive layer; said overcoat layer comprising at least a matrix, wherein the conductive layer and/or the overcoat layer comprises at least a  $\dot{A}$ -conjugated conductive polymer. The invention also concerns a method for production of said electrode assembly and electronic devices comprising said electrode assembly.

IPC 8 full level  
**H01B 1/02** (2006.01); **H01B 1/12** (2006.01); **H01B 1/22** (2006.01)

CPC (source: EP)  
**H01B 1/02** (2013.01); **H01B 1/124** (2013.01); **H01B 1/22** (2013.01)

Citation (applicant)  

- US 2008259262 A1 20081023 - JONES DAVID [US], et al
- US 2014203223 A1 20140724 - IKADA TOMOTAKE [JP], et al
- SUN ET AL.: "Crystalline silver nanowires by soft solution processing", NANOLETTERS, vol. 2, no. 2, 2002, pages 165 - 168, XP008072569, DOI: doi:10.1021/nl010093y

Citation (search report)  

- [X] WO 2013036038 A2 20130314 - LG INNOTEK CO LTD [KR], et al
- [X] US 2012138913 A1 20120607 - ALSAYED AHMED [US], et al
- [X] EP 2832785 A1 20150204 - SAMSUNG SDI CO LTD [KR]
- [X] WO 2013173070 A1 20131121 - 3M INNOVATIVE PROPERTIES CO [US], et al

Cited by  
JP2020059837A

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